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(71) Applicants (for all designated States except US):
KABUSHIKI KAISHA TOSHIBA [JP/JP]; 1-1-1,
Shibaura, Minato-ku, Tokyo 105-8001 (JP). **SHOWA**
DENKO K.K [JP/JP]; 13-9, Shabadaimon 1-chome,
Minato-ku, Tokyo 105-8518 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **MAEDA, Tomoyuki [JP/JP]**; c/o Kabushiki Kaisha Toshiba, Ome

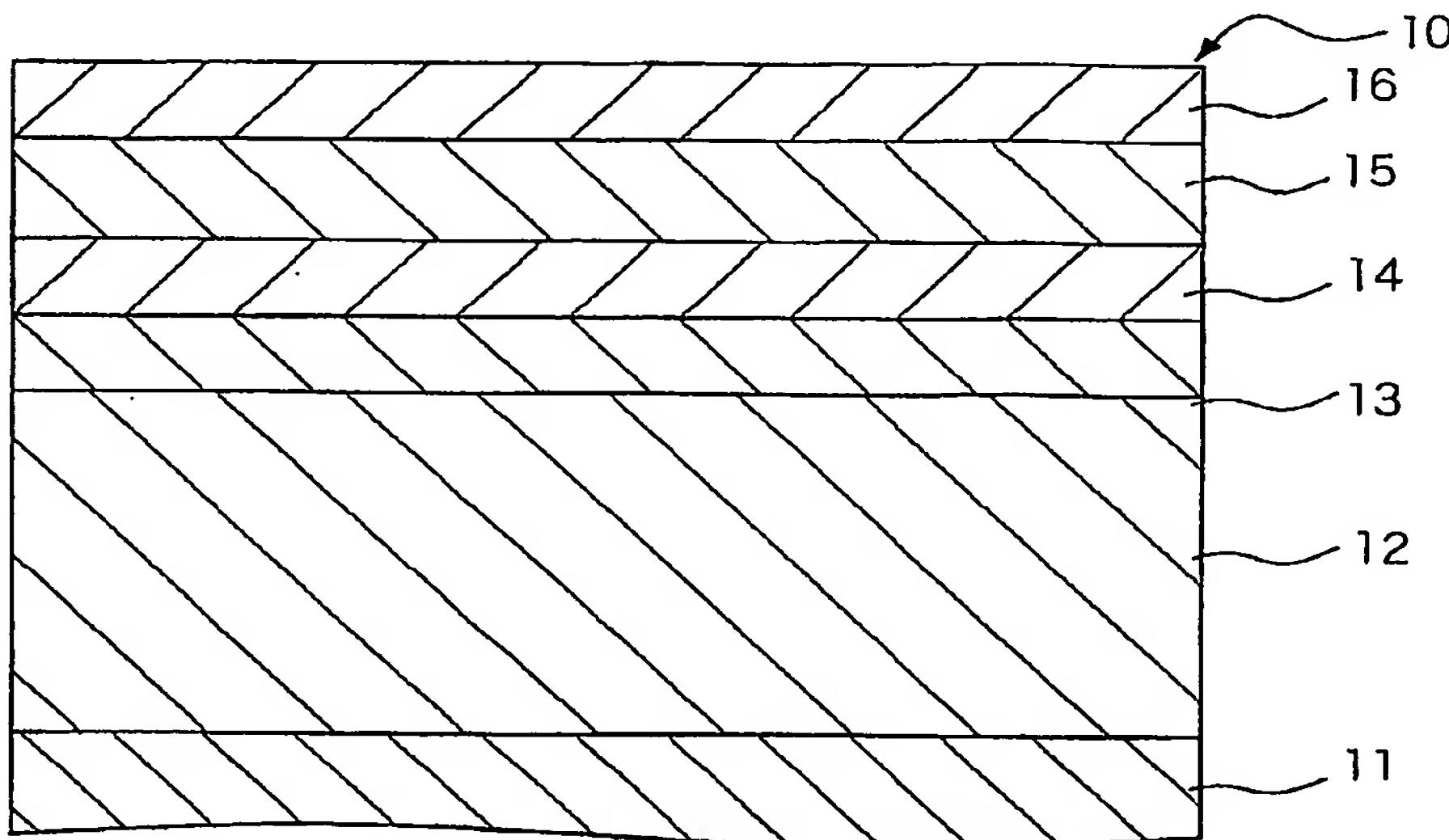
Complex, 2-9, Suehiro-cho, Ome-shi, Tokyo 143-0025 (JP). **OIKAWA, Soichi [JP/JP]**; c/o Kabushiki Kaisha Toshiba, Ome Complex, 2-9, Suehiro-cho, Ome-shi, Tokyo 143-0025 (JP). **IWASAKI, Takeshi [JP/JP]**; c/o Kabushiki Kaisha Toshiba, Ome Complex, 2-9, Suehiro-cho, Ome-shi, Tokyo 143-0025 (JP). **NAKAMURA, Futoshi [JP/JP]**; c/o Kabushiki Kaisha Toshiba, Ome Complex, 2-9, Suehiro-cho, Ome-shi, Tokyo 143-0025 (JP). **SAKAI, Hiroshi [JP/JP]**; c/o Showa Denko HD K.K., 5-1, Yawata Kaigan-dori, Ichihara-shi, Chiba 290-0067 (JP). **SHIMIZU, Kenji [JP/JP]**; c/o Showa Denko HD K.K., 5-1, Yawata Kaigan-dori, Ichihara-shi, Chiba 290-0067 (JP). **SAKAWAKI, Akira [JP/JP]**; c/o Showa Denko HD K.K., 5-1, Yawata Kaigan-dori, Ichihara-shi, Chiba 290-0067 (JP).

(74) Agents: **SHIGA, Masatake et al.**; 2-3-1 Yaesu, Chuo-ku, Tokyo 104-8453 (JP).

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(54) Title: PERPENDICULAR MAGNETIC RECORDING MEDIUM, MANUFACTURING METHOD THEREFOR, AND MAGNETIC READ/WRITE APPARATUS USING THE SAME



(57) Abstract: A perpendicular magnetic recording medium includes: a substrate; at least one underlayer formed above the substrate; and a perpendicular magnetic recording layer formed above the at least one underlayer, an easy magnetization axis of the perpendicular magnetic recording layer being oriented perpendicular to the substrate, the perpendicular magnetic recording layer including magnetic crystal particles and grain boundaries surrounding the magnetic crystal particles, wherein the grain boundaries contain an oxide of silicon and at least one element selected from the group consisting of Li, Na, K, Rb, Cs, Ca, Sr, and Ba, and the ratio of a total amount of substance of Si, Li, Na, K, Rb, Cs, Ca, Sr, and Ba in the perpendicular magnetic recording layer is no less than 1 mol% and no more than 20 mol%.

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